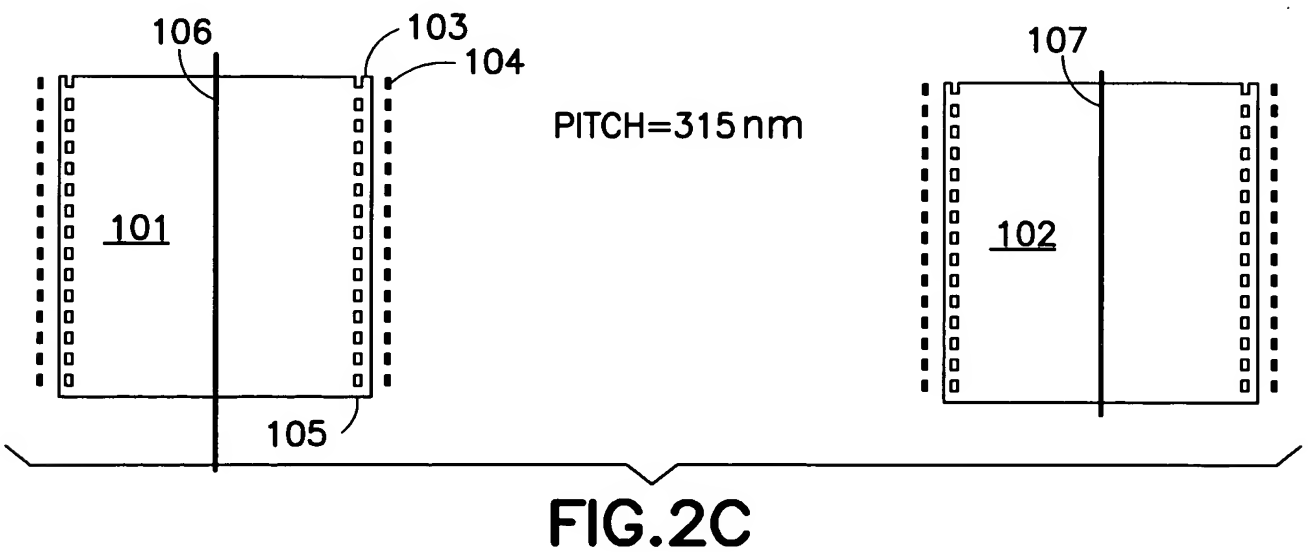
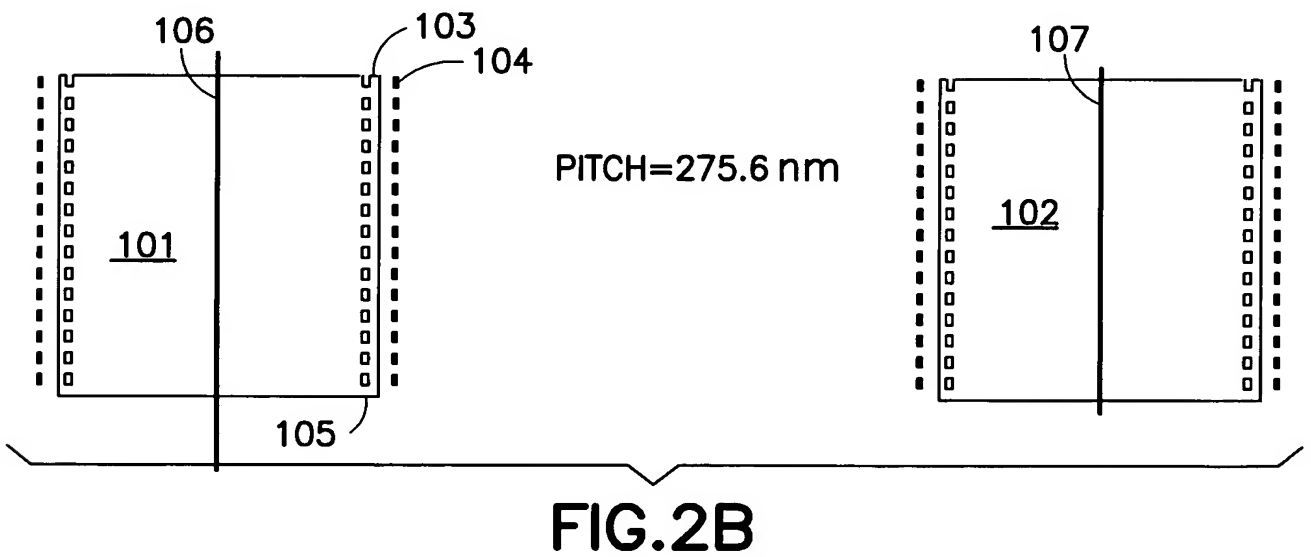
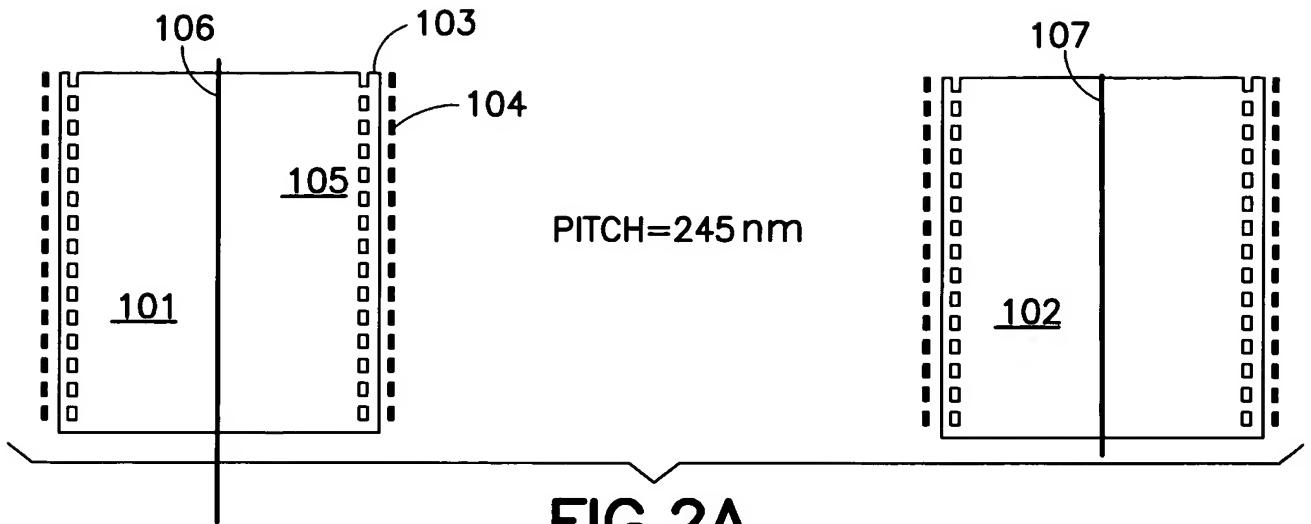
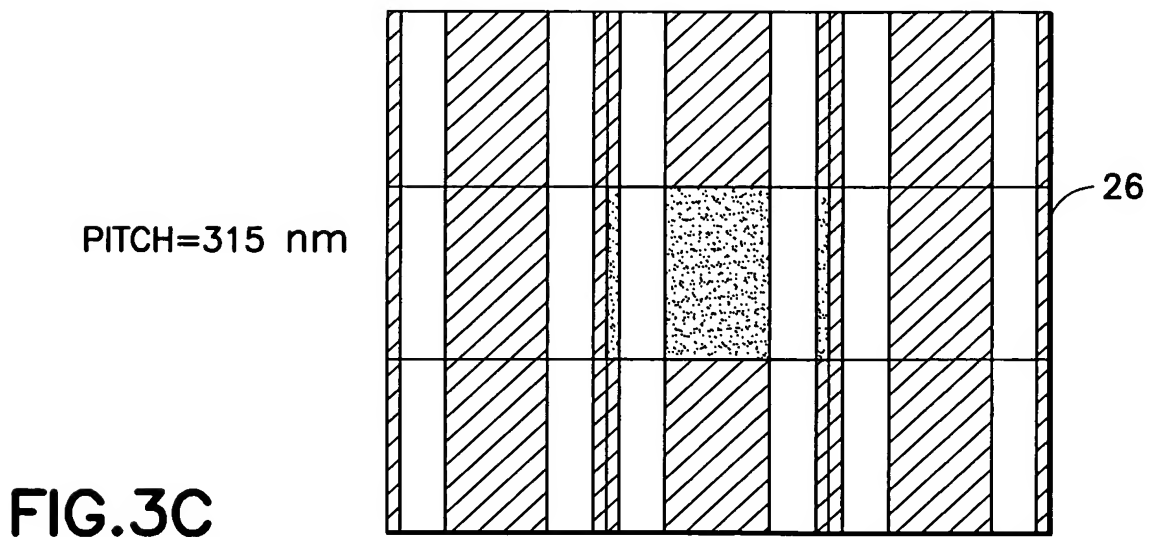
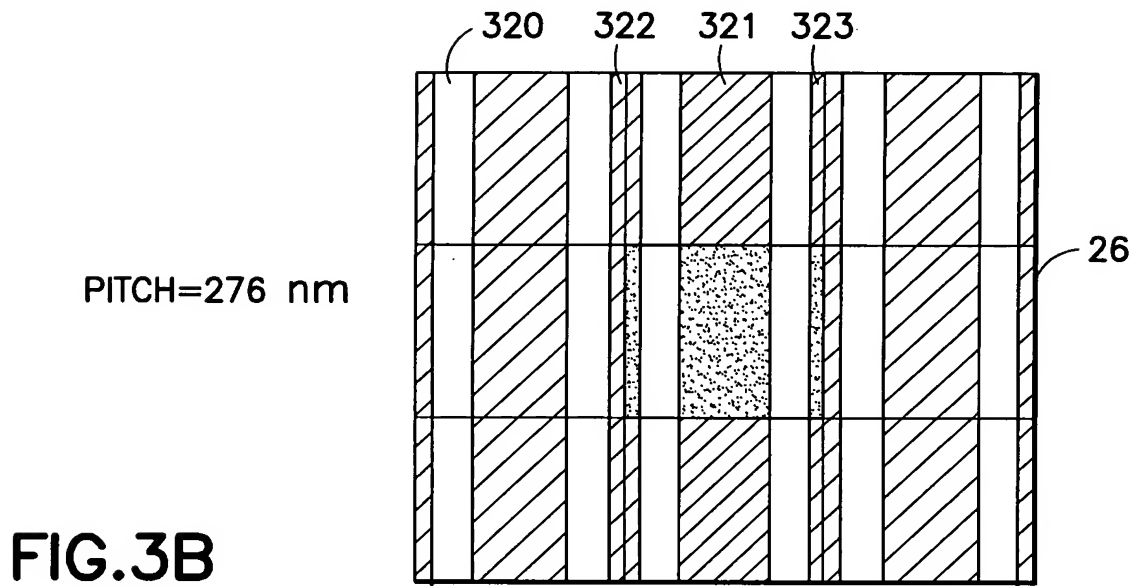
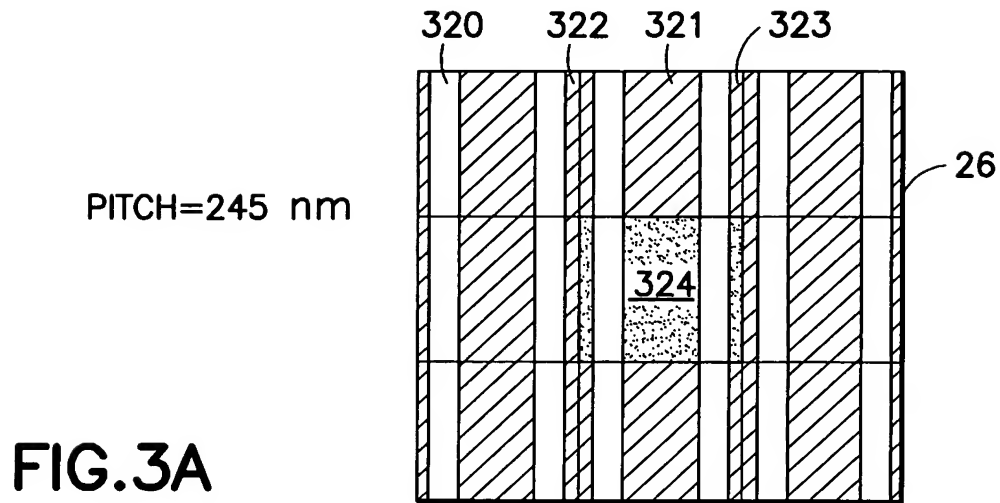


**FIG.1**  
PRIOR ART





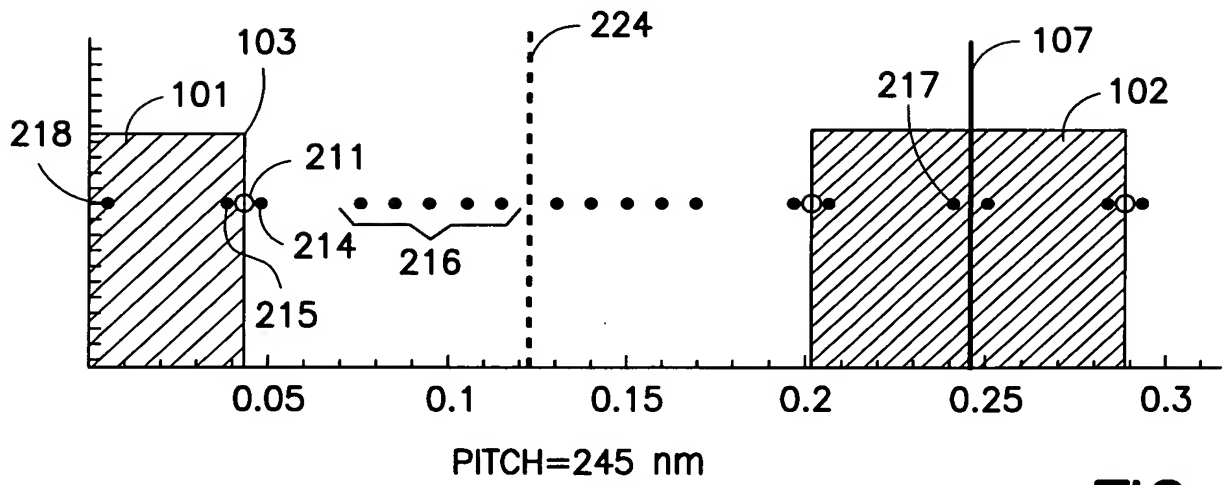


FIG. 4A

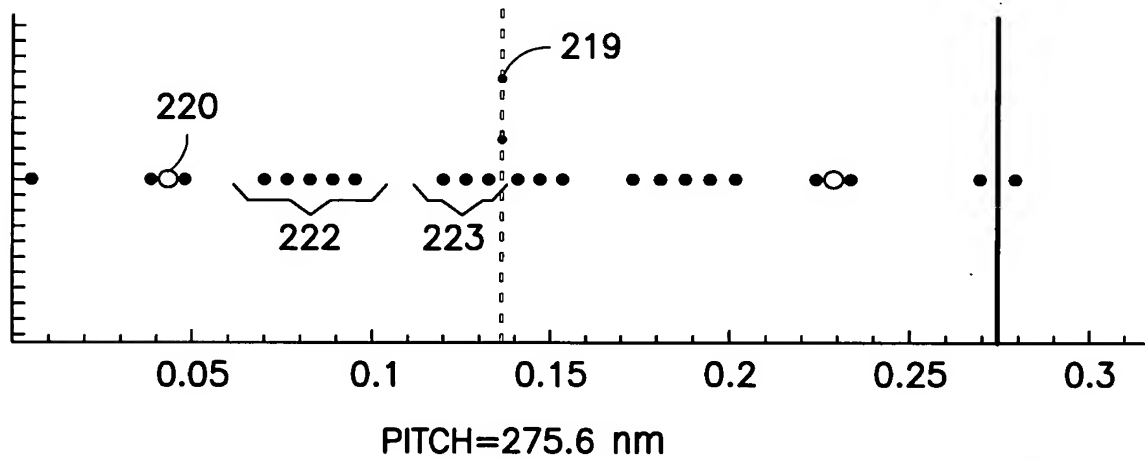


FIG. 4B

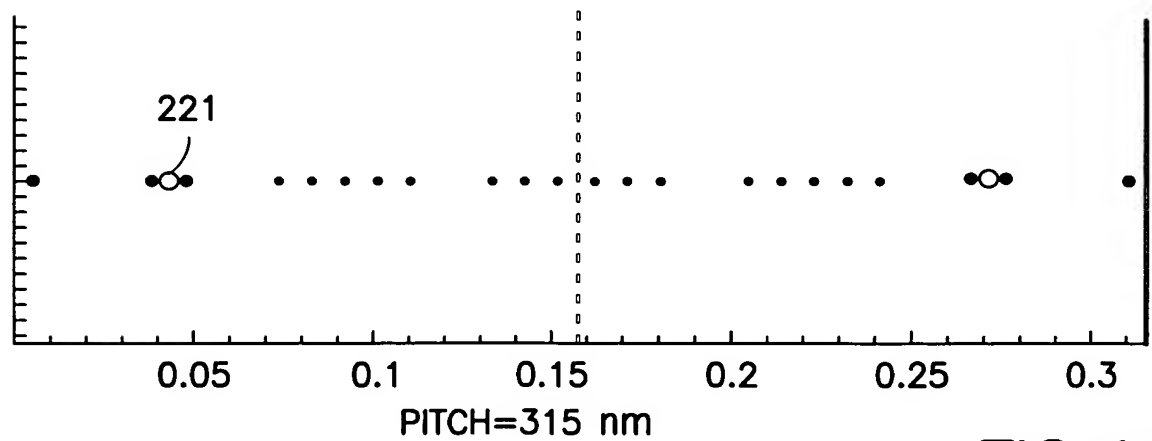
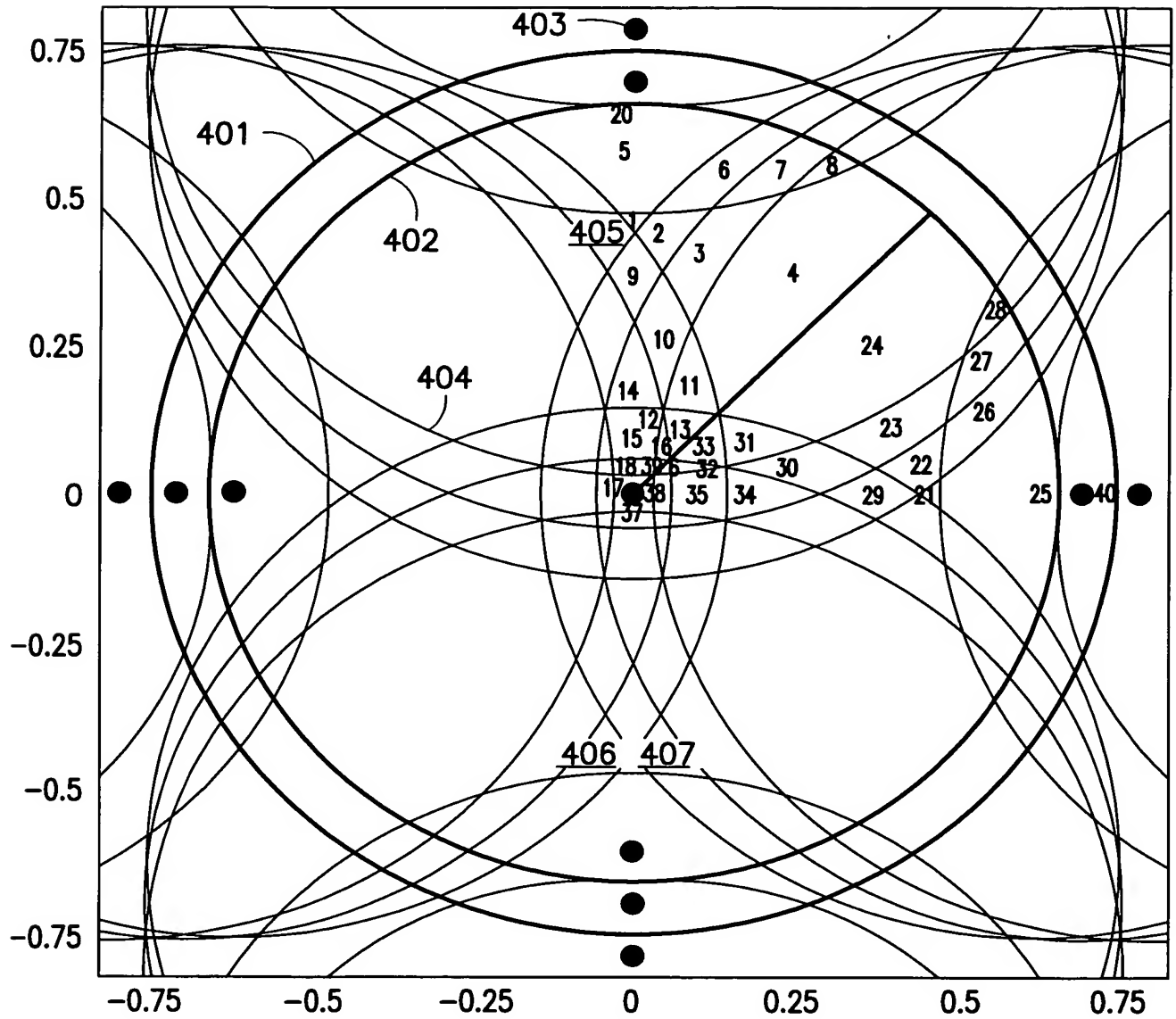


FIG. 4C



**FIG.5**  
PRIOR ART

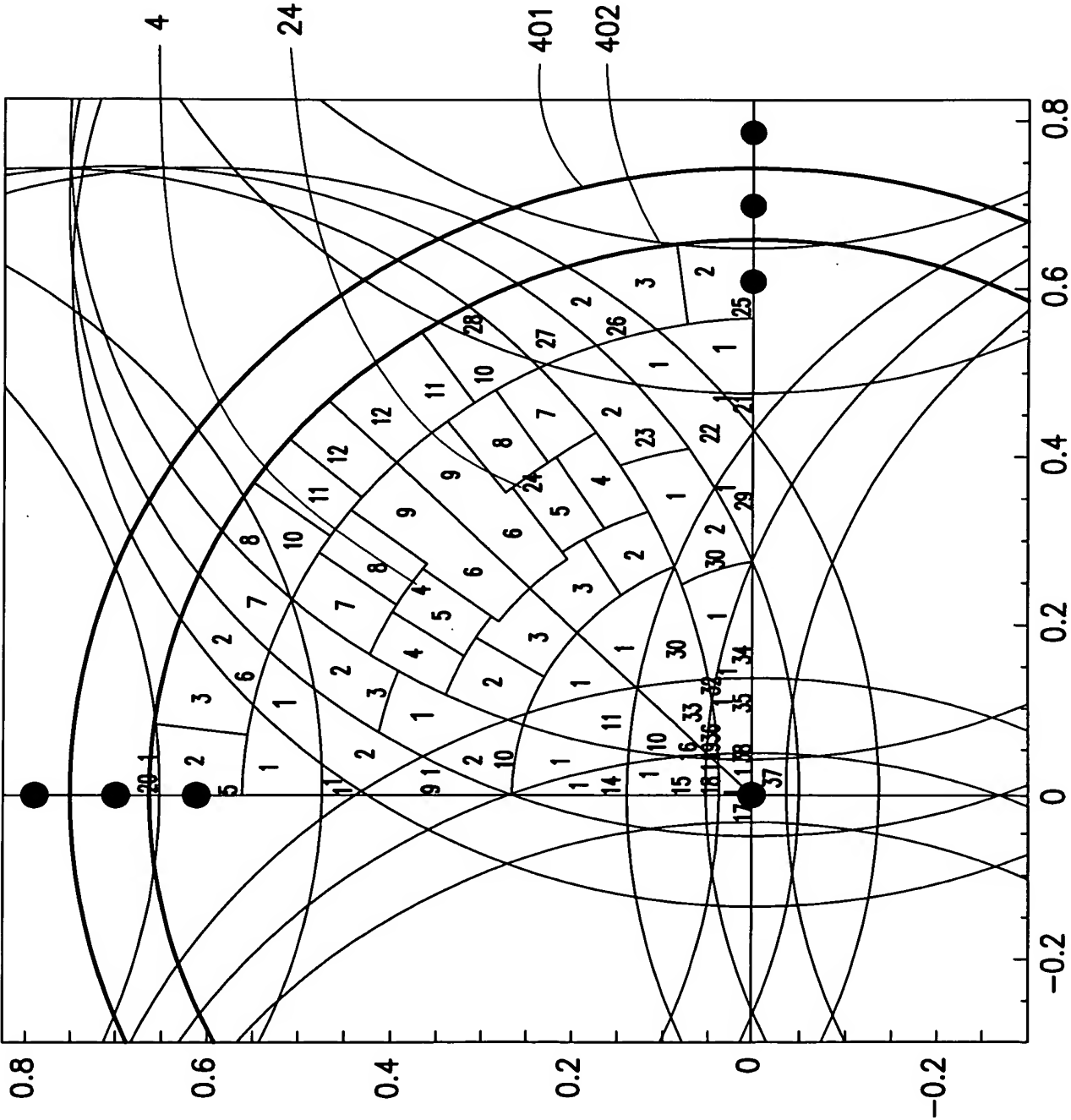


FIG.6

SOURCE 4-6 IN FOCUS

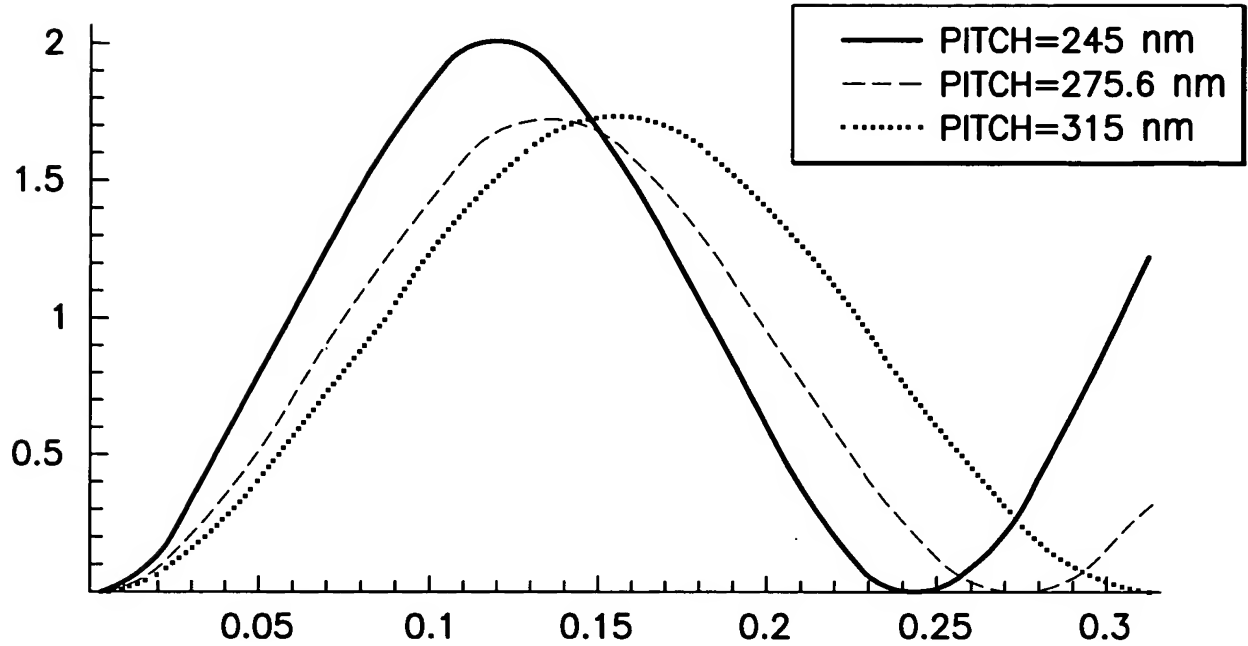


FIG.7

SOURCE 4-6 AT 0.3  $\mu\text{m}$  DEFOCUS

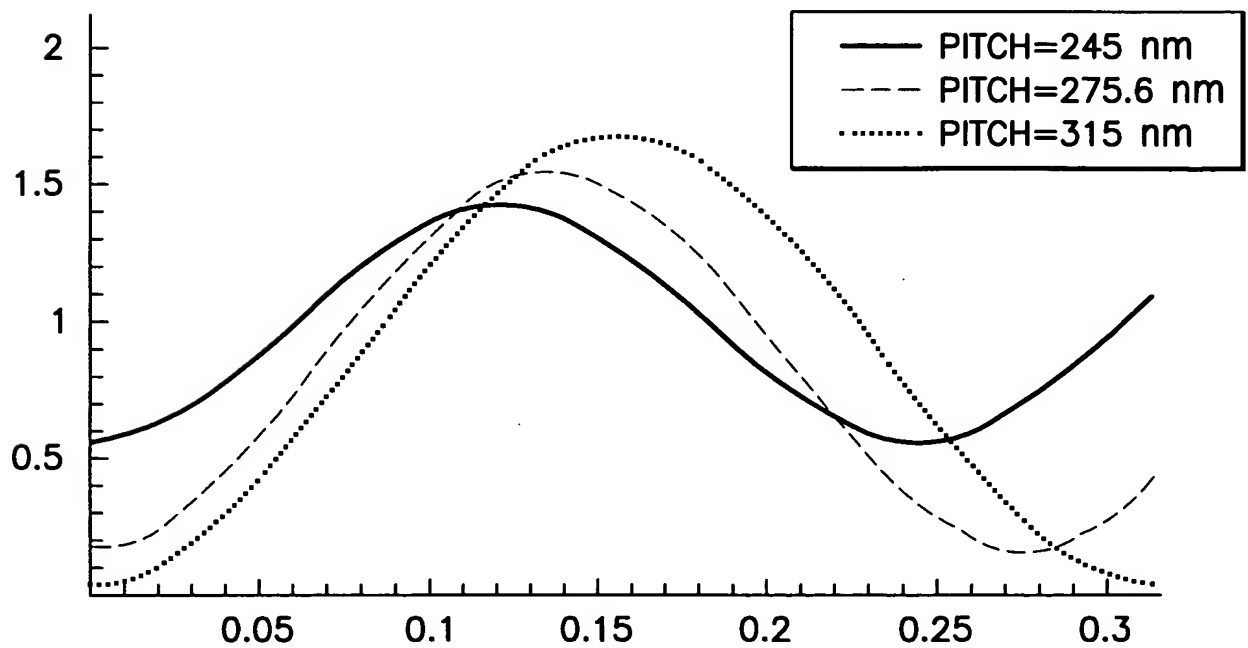


FIG.8

SOURCE 3-2 IN FOCUS

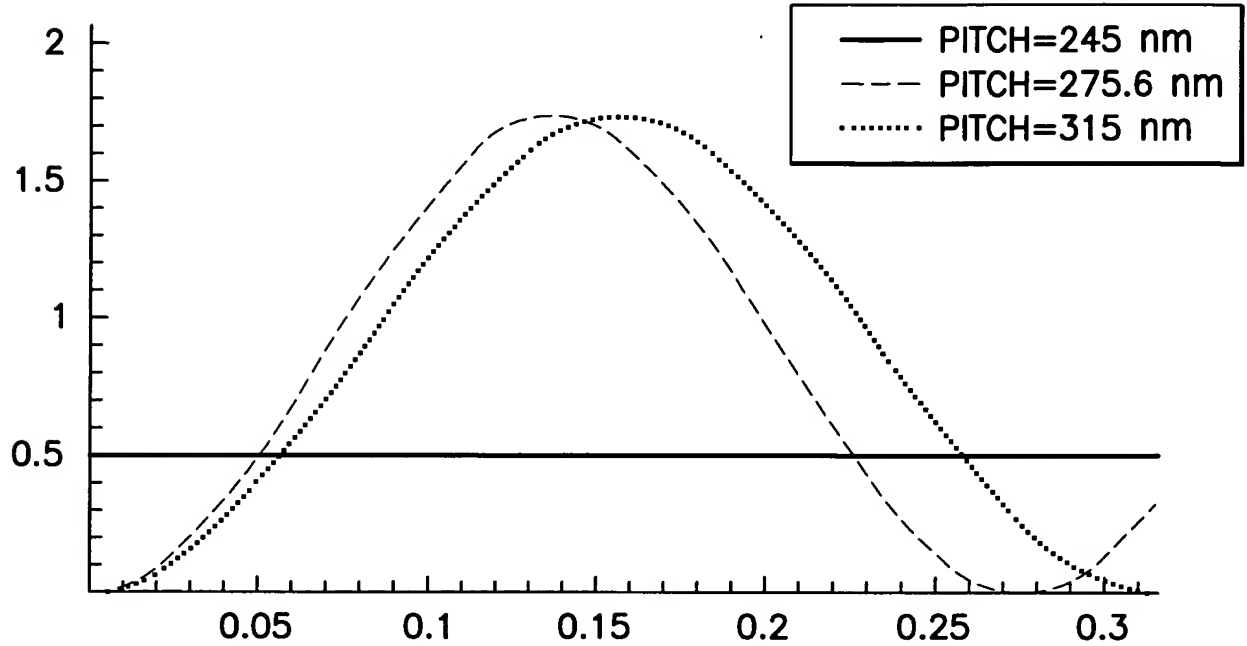


FIG.9

SOURCE 3-2 AT 0.3  $\mu\text{m}$  DEFOCUS

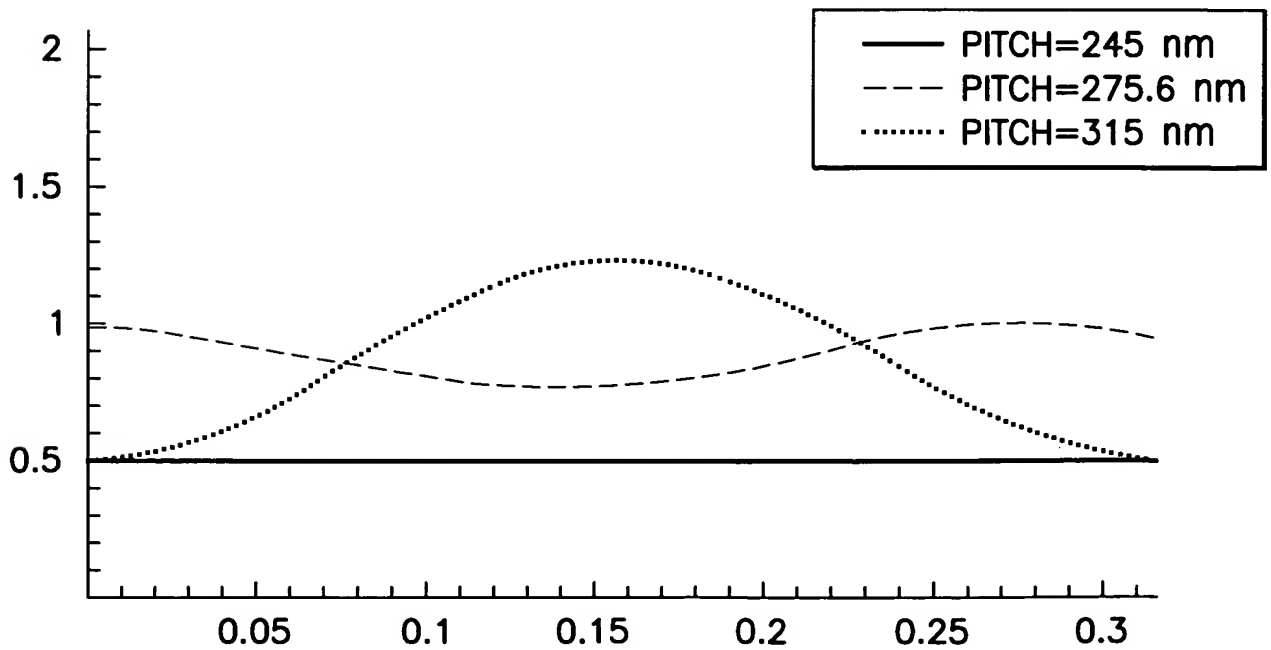


FIG.10



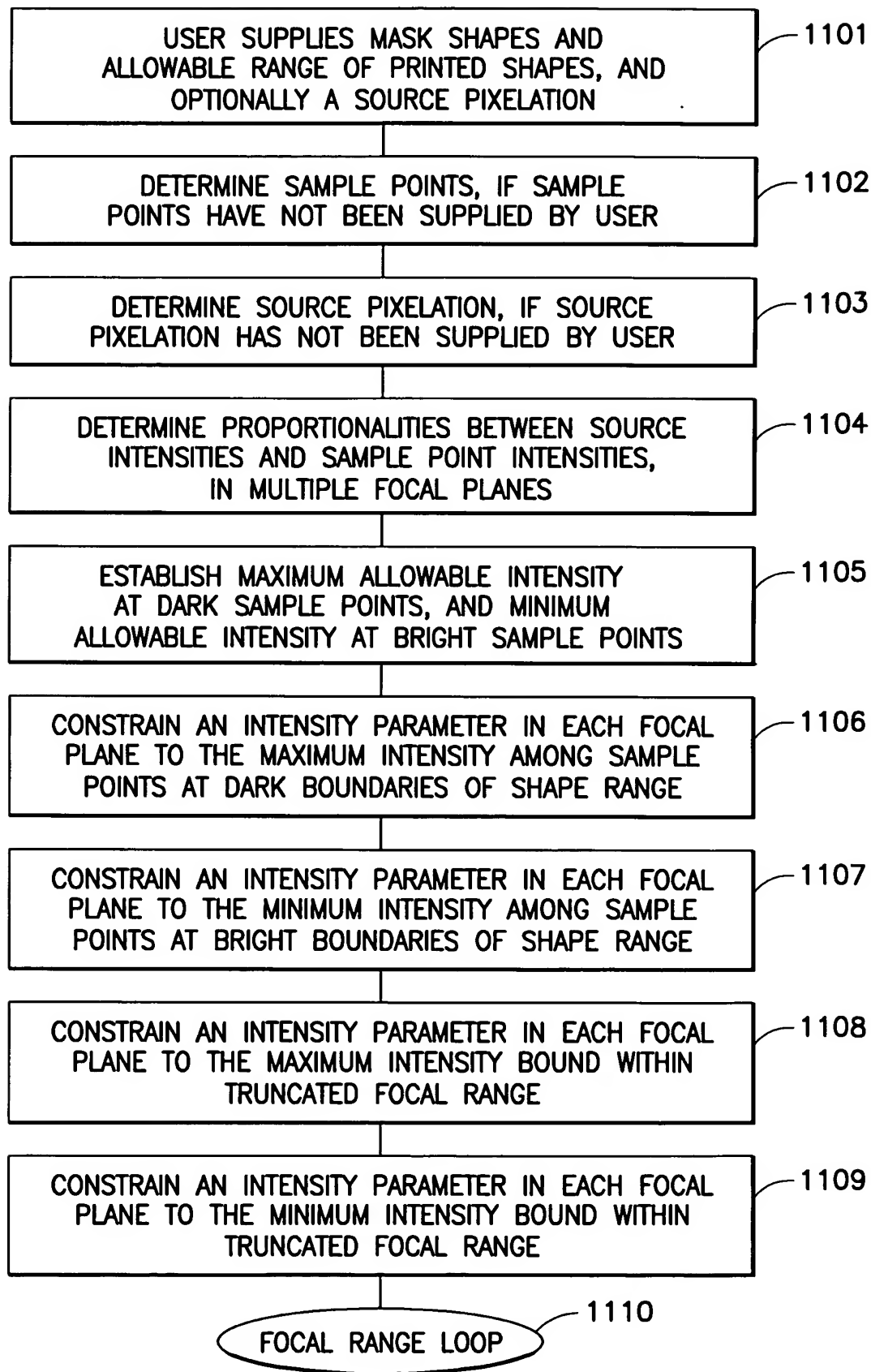
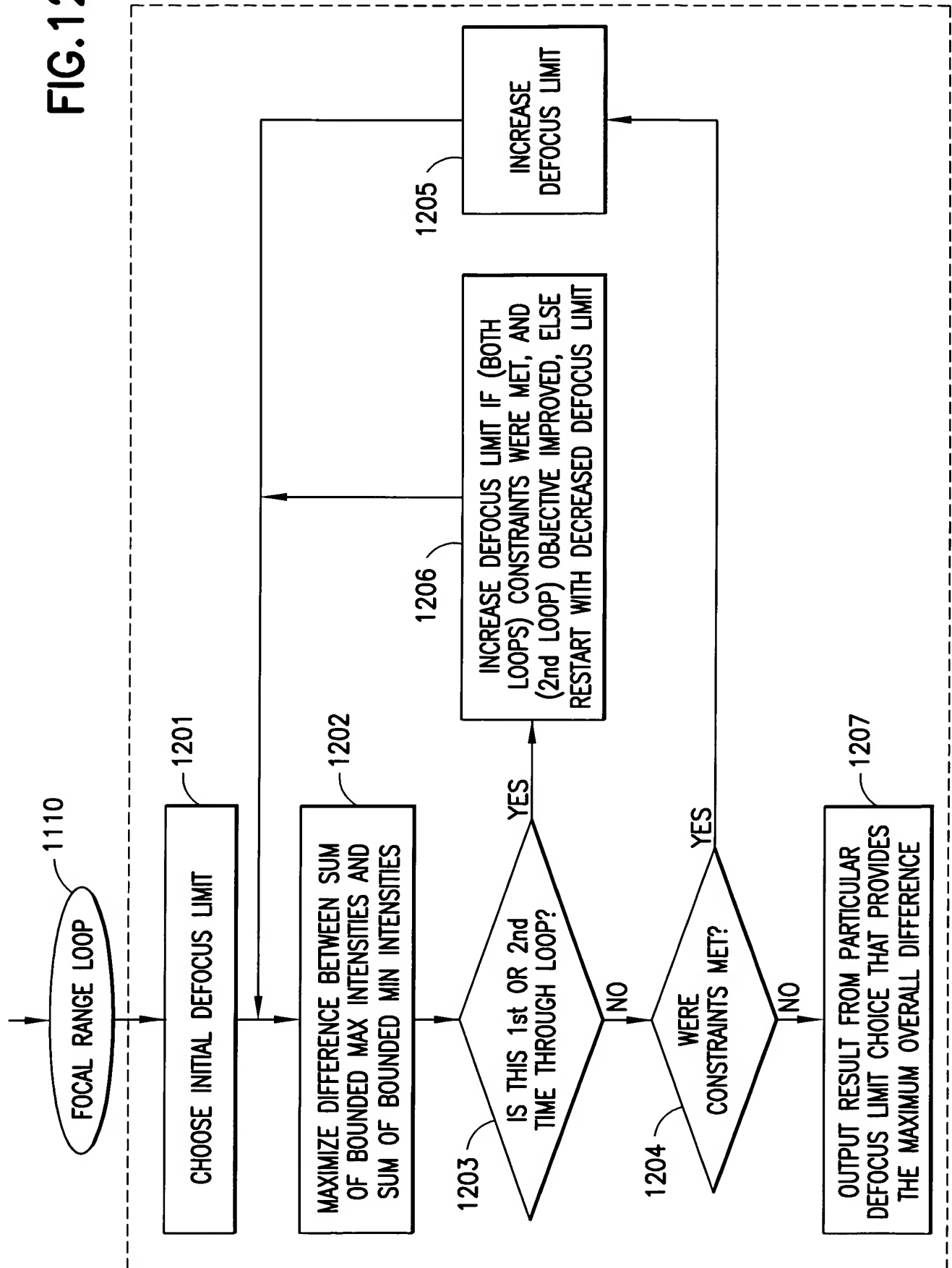
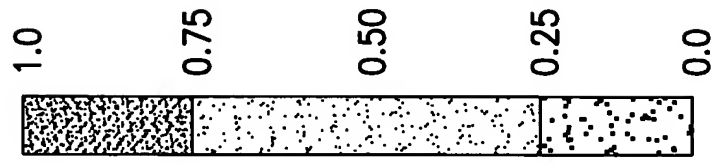
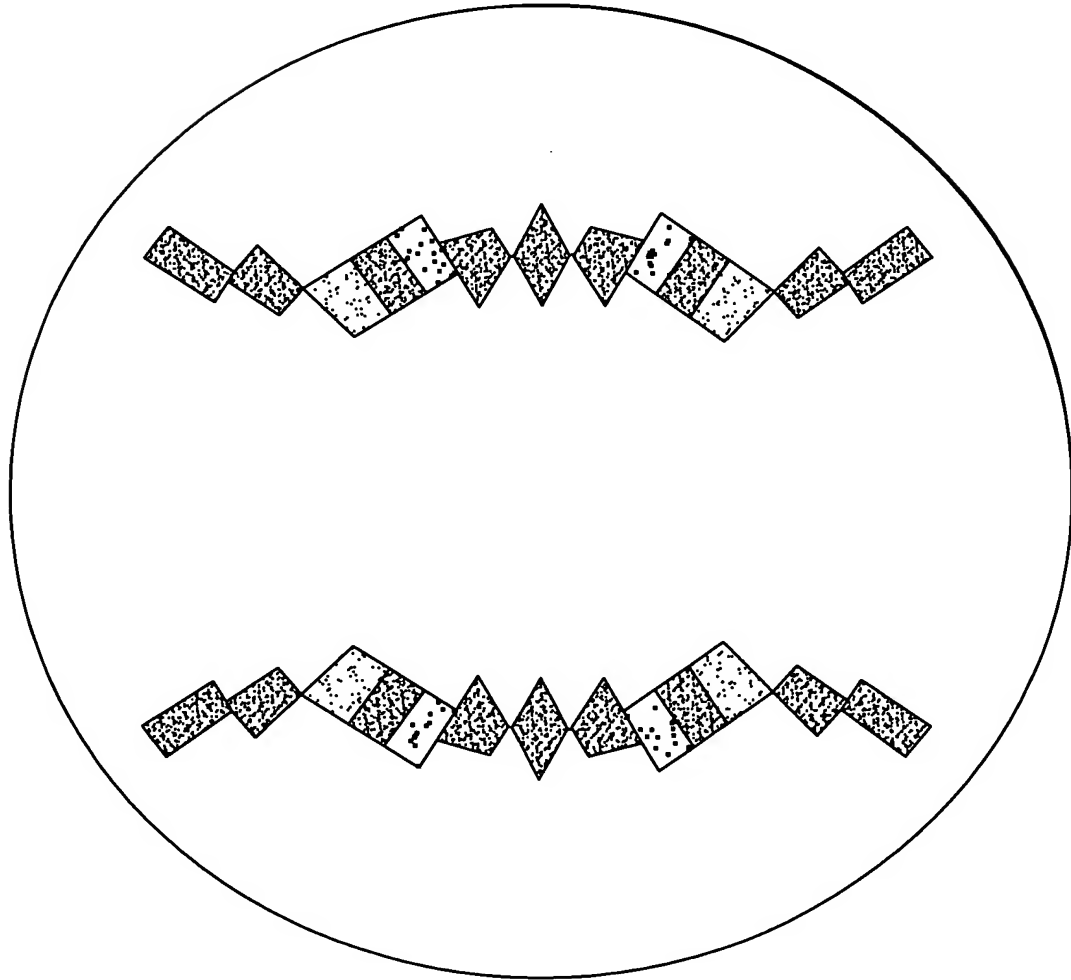


FIG. 11

FIG.12



GLOBALLY OPTIMIZED SOURCE TO MAXIMIZE  
COMMON WINDOW. CD IS 87.5 nm,  
WITH  $\pm 9\%$  CD TOLERANCE.  
PITCHES ARE 245nm - 315nm,  
NA=0.75,  $\lambda = 193$  nm



PROCESS WINDOW IS 24.1% -  $\mu\text{m}$   
10% PUPIL FILL (WITHIN  $\delta = 0.88$ ),  
VERTICAL PATTERNS

FIG.13

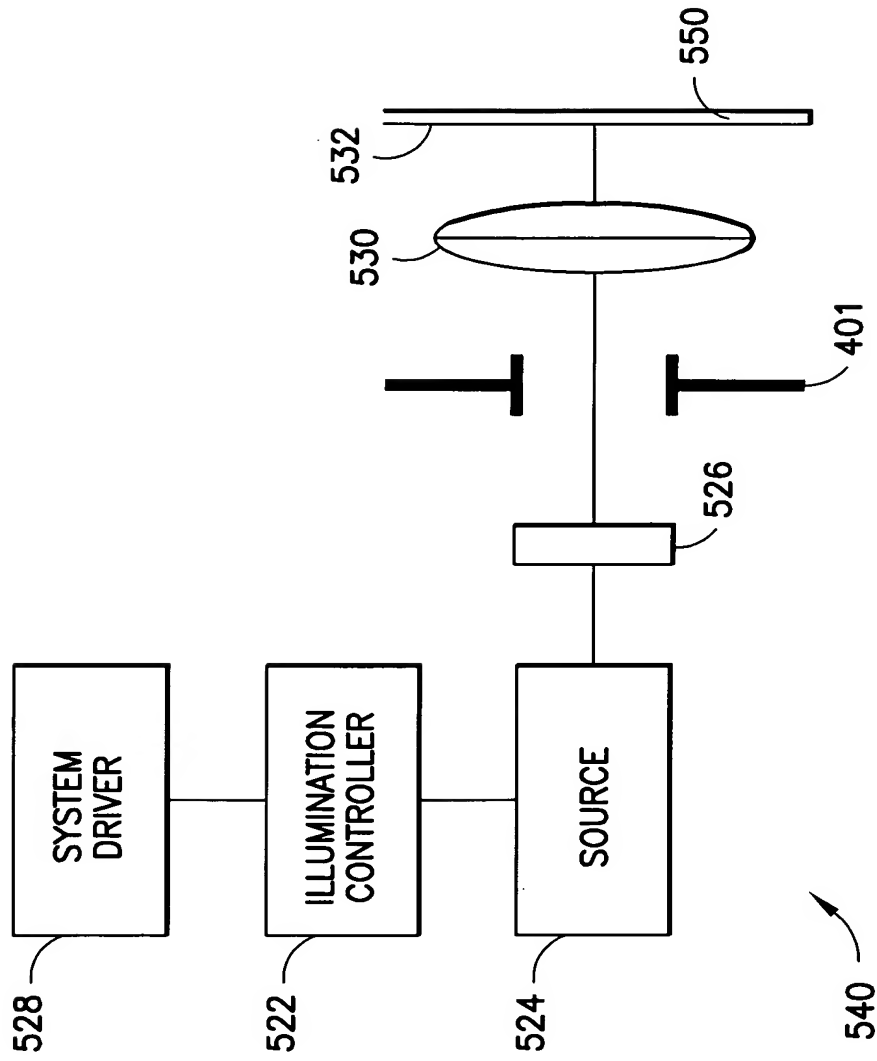


FIG.14